

10/698, 648, 2+3  
=> d his  
Registry file  
CA/STK search, Nb-  
lactone  
In New claims 13-15,  
1-19-06, RPT

(FILE 'HOME' ENTERED AT 14:40:46 ON 18 JAN 2006)

FILE 'REGISTRY' ENTERED AT 14:40:54 ON 18 JAN 2006

L1 25 S CYCLOPENTYL METHACRYLATE  
L2 16 S CYCLOPENTYL ACRYLATE  
L3 167 S ADAMANTYL METHACRYLATE  
L4 54 S ADAMANTYL ACRYLATE  
L5 0 S ADAMANTYLACRYLATE  
L6 1303 S CYCLOHEXYL METHACRYLATE  
L7 378 S CYCLOHEXYL ACRYLATE  
L8 0 S ETHYLADAMANTYL ACRYLATE  
L9 2 S ETHYLADAMANTYL METHACRYLATE  
L10 10 S METHYLADAMANTYL METHACRYLATE  
L11 1 S (L1 OR L2) AND (L3 OR L4)  
L12 6 S (L6 OR L7) AND (L9 OR L10 OR L3 OR L4)  
L13 2 S L12 AND 2/NC

FILE 'CAPLUS' ENTERED AT 14:45:38 ON 18 JAN 2006

L14 12 S L13  
L15 2 S 581092-39-9/RN

FILE 'REGISTRY' ENTERED AT 14:47:44 ON 18 JAN 2006

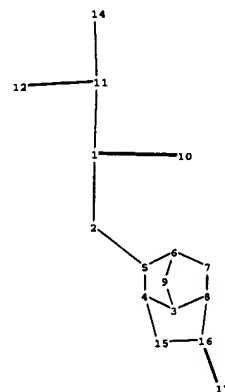
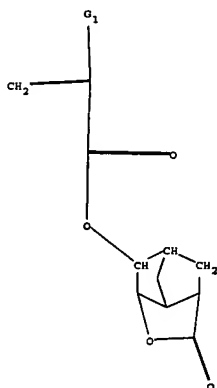
L16 1 S (L1 OR L2) AND (L3 OR L4 OR L9 OR L10)

FILE 'CAPLUS' ENTERED AT 14:49:15 ON 18 JAN 2006

L17 1 S L16

=>

8/10/02



chain nodes :

1 2 10 11 12 14 17

ring nodes :

3 4 5 6 7 8 9 15 16

chain bonds :

1-2 1-10 1-11 2-5 11-12 11-14 16-17

ring bonds :

3-4 3-8 3-9 4-5 4-15 5-6 6-7 6-9 7-8 8-16 15-16

exact/norm bonds :

4-15 8-16 11-14 15-16 16-17

exact bonds :

1-2 1-10 1-11 2-5 3-4 3-8 3-9 4-5 5-6 6-7 6-9 7-8 11-12

G1:H,CH3

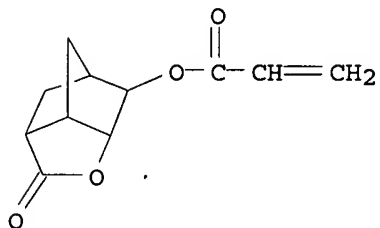
Match level :

1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:Atom 7:Atom 8:Atom 9:Atom 10:CLASS 11:Atom  
12:Atom 14:Atom 15:Atom 16:Atom 17:Atom

L4 ANSWER 29 OF 29 REGISTRY COPYRIGHT 2006 ACS on STN  
 RN 254900-09-9 REGISTRY  
 ED Entered STN: 04 Feb 2000  
 CN 2-Propenoic acid, 2-methyl-, 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl ester,  
 polymer with hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl  
 2-propenoate (9CI) (CA INDEX NAME)  
 OTHER CA INDEX NAMES:  
 CN 2-Propenoic acid, hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl  
 ester, polymer with 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl  
 2-methyl-2-propenoate (9CI)  
 OTHER NAMES:  
 CN **5-Acryloyloxy-2,6-norbornanecarbolactone-2-methyl-2-adamantyl**  
**methacrylate copolymer**  
 MF (C15 H22 O2 . C11 H12 O4)x  
 CI PMS  
 PCT Polyacrylic  
 SR CA  
 LC STN Files: CA, CAPLUS, USPAT2, USPATFULL

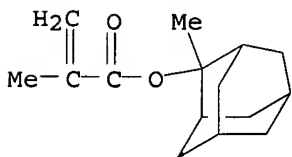
CM 1

CRN 242129-35-7  
 CMF C11 H12 O4



CM 2

CRN 177080-67-0  
 CMF C15 H22 O2



3 REFERENCES IN FILE CA (1907 TO DATE)  
 3 REFERENCES IN FILE CAPLUS (1907 TO DATE)

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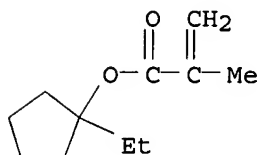
L31 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2006 ACS on STN  
 RN 854908-07-9 REGISTRY  
 ED Entered STN: 13 Jul 2005  
 CN 2-Propenoic acid, 2-methyl-, 1-ethylcyclopentyl ester, polymer with  
 hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl 2-propenoate and  
 3-hydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl 2-methyl-2-propenoate (9CI) (CA  
 INDEX NAME)

OTHER NAMES:

CN **5-Acryloyloxy-2,6-norbornanecarbolactone-1-ethylcyclopentyl  
 methacrylate-3-hydroxy-1-adamantyl methacrylate copolymer**  
 MF (C14 H20 O3 . C11 H18 O2 . C11 H12 O4)x  
 CI PMS  
 PCT Polyacrylic  
 SR CA  
 LC STN Files: CA, CAPLUS

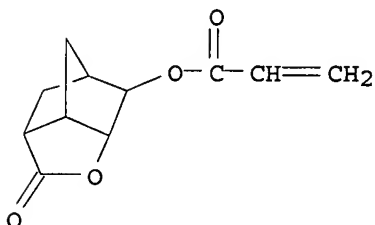
CM 1

CRN 266308-58-1  
 CMF C11 H18 O2



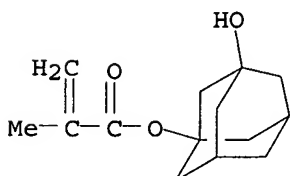
CM 2

CRN 242129-35-7  
 CMF C11 H12 O4



CM 3

CRN 115372-36-6  
 CMF C14 H20 O3



\*\*PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT\*\*

1 REFERENCES IN FILE CA (1907 TO DATE)  
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

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L32 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2006 ACS on STN  
 AN 2005:540707 CAPLUS  
 DN 143:86697  
 TI Resist polymer solution and process for producing the same  
 IN Yamagishi, Takanori; Baba, Hiromitsu  
 PA Maruzen Petrochemical Co., Ltd., Japan  
 SO PCT Int. Appl., 27 pp.  
 CODEN: PIXXD2  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

|      | PATENT NO.  | KIND | DATE     | APPLICATION NO. | DATE     |
|------|---|------|----------|-----------------|----------|
| PI   | WO 2005057288   | A1   | 20050623 | WO 2004-JP18494 | 20041210 |
|      | W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW |      |          |                 |          |
|      | RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG  |      |          |                 |          |
|      | JP 2005173252   | A2   | 20050630 | JP 2003-413627  | 20031211 |
|      | JP 3694692  | B2   | 20050914 |                 |          |
| PRAI | JP 2003-413627  | A    | 20031211 |                 |          |

AB A resist polymer solution comprising a resist polymer containing a repeating unit

decomposed by the action of an acid so as to be soluble in alkali and a repeating unit having a polar group, the resist polymer dissolved in a solvent for coating film formation, wherein the amount of impurities whose b.p. is not higher than that of the solvent for coating film formation is  $\leq 1$  mass% based on the resist polymer. Further, there is provided a process for producing a resist polymer solution, comprising the step (1) of re-dissolving a solid matter containing a resist polymer in a solvent for coating film formation (a) and/or a solvent (b) whose b.p. at atmospheric pressure is not higher than that of the solvent (a); and the impurity removing step (2) of distilling off the solvent (b) and/or any excess amount of solvent (a) in vacuum from the re-dissoln. solution obtained in the step (1).

IT 854908-07-9P, 5-Acryloyloxy-2,6-norbornanecarbolactone-1-ethylcyclopentyl methacrylate-3-hydroxy-1-adamantyl methacrylate copolymer  
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (resist polymer solution and process for producing the same)

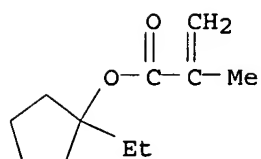
RN 854908-07-9 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-ethylcyclopentyl ester, polymer with hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl 2-propenoate and 3-hydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 266308-58-1

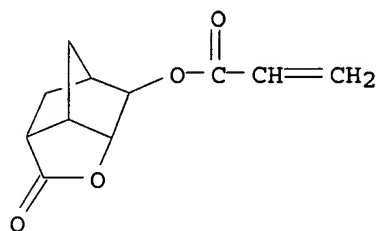
CMF C11 H18 O2



CM 2

CRN 242129-35-7

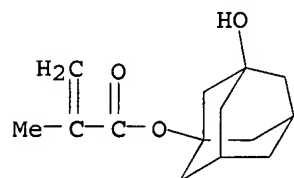
CMF C11 H12 O4



CM 3

CRN 115372-36-6

CMF C14 H20 O3



RE.CNT 9 THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD  
ALL CITATIONS AVAILABLE IN THE RE FORMAT

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L15 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2006 ACS on STN

AN 2004:816602 CAPLUS

DN 141:322563

TI Polysiloxane substituted with blocked acidic group and photocurable composition for formation of pattern

IN Takahashi, Hideyuki; Ishizeki, Kenji

PA Asahi Glass Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 19 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

|      | PATENT NO.    | KIND | DATE     | APPLICATION NO. | DATE     |
|------|---------------|------|----------|-----------------|----------|
| PI   | JP 2004277493 | A2   | 20041007 | JP 2003-68215   | 20030313 |
| PRAI | JP 2003-68215 |      | 20030313 |                 |          |

AB The polymer has polysiloxane structure (SiR<sub>1</sub>R<sub>2</sub>O)<sub>n</sub>SiR<sub>1</sub>R<sub>2</sub>R<sub>3</sub> [I; R<sub>1</sub>, R<sub>2</sub> = H, (cyclo)alkyl, aryl; R<sub>3</sub> = H, C<sub>1</sub>-10 organic group; n = 1-200] and 1-95 weight% of blocked acidic substituents. The polysiloxane may be substituted with fluoroalkyl on ≥2 H. The photocurable composition contains the polysiloxane, another polymer, and a photosensitive acid-generating agent. The another polymer is substituted with blocked acidic groups and is free from structure I and from I whose ≥2 H are replaced by F-substituted C≤20 alkyl. The composition is useful for a precisely patterned mask for preparation of elec. circuits, which shows enhanced ink repellency.

IT 581092-39-9P, Cyclohexyl methacrylate-2-methyl-2-adamantyl methacrylate copolymer

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(photocurable composition containing polysiloxane substituted with blocked acidic group and)

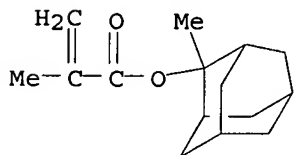
RN 581092-39-9 CAPLUS

CN 2-Propenoic acid, 2-methyl-, cyclohexyl ester, polymer with 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 177080-67-0

CMF C15 H22 O2

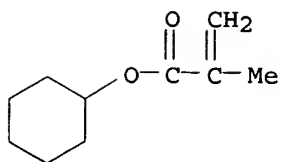


CM 2

CRN 101-43-9

CMF C10 H16 O2





L15 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2006 ACS on STN  
 AN 2003:673878 CAPLUS  
 DN 139:188322  
 TI Chemically amplified photoresists for ArF excimer laser lithography and polymers therefor  
 IN Arita, Yasushi  
 PA Sumitomo Bakelite Co., Ltd., Japan  
 SO Jpn. Kokai Tokkyo Koho, 10 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

|      | PATENT NO.    | KIND | DATE     | APPLICATION NO. | DATE     |
|------|---------------|------|----------|-----------------|----------|
| PI   | JP 2003238629 | A2   | 20030827 | JP 2002-41297   | 20020219 |
| PRAI | JP 2002-41297 |      | 20020219 |                 |          |

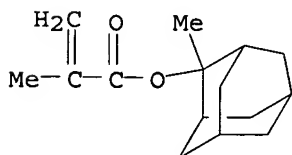
AB The polymers are a:b:c (molar ratio) cyclohexyl (meth)acrylate-2-methyl-2-adamantyl (meth)acrylate-(meth)acrylic acid derivative copolymers satisfying  $a/(a + b + c)$  0.2-0.8,  $b/(a + b + c)$  0.05-0.5, and  $c/(a + b + c)$  0-0.5, and may satisfy  $M_n$  1000-100,000 and polydispersity  $>1.0$  and  $\leq 2.0$ . The (meth)acrylic acid derivs. are  $RC:CH_2CO_2R'$  [ $R' = H, C1-12$  (cyclo)alkyl, alkoxyalkyl, cyclic ether, cyclic ester]. Chemical amplified photoresists containing the polymers show excellent sensitivity to ArF excimer laser light and superior high resolution

IT **581092-39-9P**, Cyclohexyl methacrylate-2-methyl-2-adamantylmethacrylate copolymer  
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (high-sensitivity and -resolution chemical amplified photoresists for ArF excimer laser lithog.)

RN 581092-39-9 CAPLUS  
 CN 2-Propenoic acid, 2-methyl-, cyclohexyl ester, polymer with 2-methyltricyclo[3.3.1.1<sup>3,7</sup>]dec-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

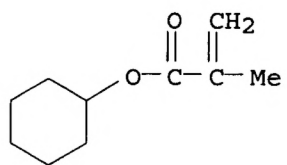
CM 1

CRN 177080-67-0  
 CMF C15 H22 O2



CM 2

CRN 101-43-9  
 CMF C10 H16 O2



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bib ab hitstr

L17 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2006 ACS on STN  
AN 2005:540707 CAPLUS  
DN 143:86697  
TI Resist polymer solution and process for producing the same  
IN Yamagishi, Takanori; Baba, Hiromitsu  
PA Maruzen Petrochemical Co., Ltd., Japan  
SO PCT Int. Appl., 27 pp.  
CODEN: PIXXD2  
DT Patent  
LA Japanese  
FAN.CNT 1

|      | PATENT NO.  | KIND | DATE     | APPLICATION NO. | DATE     |
|------|---|------|----------|-----------------|----------|
| PI   | WO 2005057288   | A1   | 20050623 | WO 2004-JP18494 | 20041210 |
|      | W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW . |      |          |                 |          |
|      | RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG  |      |          |                 |          |
|      | JP 2005173252   | A2   | 20050630 | JP 2003-413627  | 20031211 |
|      | JP 3694692  | B2   | 20050914 |                 |          |
| PRAI | JP 2003-413627  | A    | 20031211 |                 |          |

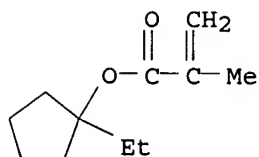
AB A resist polymer solution comprising a resist polymer containing a repeating unit

decomposed by the action of an acid so as to be soluble in alkali and a repeating unit having a polar group, the resist polymer dissolved in a solvent for coating film formation, wherein the amount of impurities whose b.p. is not higher than that of the solvent for coating film formation is  $\leq 1$  mass% based on the resist polymer. Further, there is provided a process for producing a resist polymer solution, comprising the step (1) of re-dissolving a solid matter containing a resist polymer in a solvent for coating film formation (a) and/or a solvent (b) whose b.p. at atmospheric pressure is not higher than that of the solvent (a); and the impurity removing step (2) of distilling off the solvent (b) and/or any excess amount of solvent (a) in vacuum from the re-dissoln. solution obtained in the step (1).

IT 854908-07-9P, 5-Acryloyloxy-2,6-norbornanecarbolactone-1-ethylcyclopentyl methacrylate-3-hydroxy-1-adamantyl methacrylate copolymer  
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(resist polymer solution and process for producing the same)  
RN 854908-07-9 CAPLUS  
CN 2-Propenoic acid, 2-methyl-, 1-ethylcyclopentyl ester, polymer with hexahydro-2-oxo-3,5-methano-2H-cyclopenta[b]furan-6-yl 2-propenoate and 3-hydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

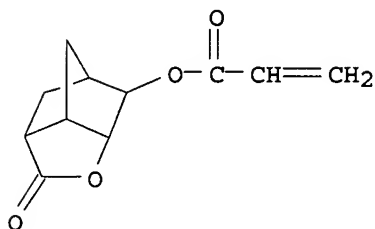
CRN 266308-58-1  
CMF C11 H18 O2



CM 2

CRN 242129-35-7

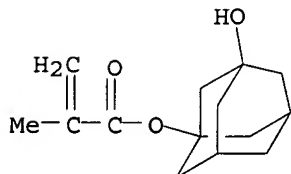
CMF C11 H12 O4



CM 3

CRN 115372-36-6

CMF C14 H20 O3



RE.CNT 9 THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD  
ALL CITATIONS AVAILABLE IN THE RE FORMAT

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(FILE 'HOME' ENTERED AT 14:40:46 ON 18 JAN 2006)

FILE 'REGISTRY' ENTERED AT 14:40:54 ON 18 JAN 2006

|     |        |  |
|-----|--------|--|
| L1  | 25 S   | CYCLOPENTYL METHACRYLATE               |
| L2  | 16 S   | CYCLOPENTYL ACRYLATE                   |
| L3  | 167 S  | ADAMANTYL METHACRYLATE                 |
| L4  | 54 S   | ADAMANTYL ACRYLATE                     |
| L5  | 0 S    | ADAMANTYLACRYLATE                      |
| L6  | 1303 S | CYCLOHEXYL METHACRYLATE                |
| L7  | 378 S  | CYCLOHEXYL ACRYLATE                    |
| L8  | 0 S    | ETHYLADAMANTYL ACRYLATE                |
| L9  | 2 S    | ETHYLADAMANTYL METHACRYLATE            |
| L10 | 10 S   | METHYLADAMANTYL METHACRYLATE           |
| L11 | 1 S    | (L1 OR L2) AND (L3 OR L4)              |
| L12 | 6 S    | (L6 OR L7) AND (L9 OR L10 OR L3 OR L4) |
| L13 | 2 S    | L12 AND 2/NC                           |

FILE 'CAPLUS' ENTERED AT 14:45:38 ON 18 JAN 2006

L14 12 S L13

L15 2 S 581092-39-9/RN

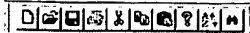
FILE 'REGISTRY' ENTERED AT 14:47:44 ON 18 JAN 2006

L16 1 S (L1 OR L2) AND (L3 OR L4 OR L9 OR L10)

FILE 'CAPLUS' ENTERED AT 14:49:15 ON 18 JAN 2006

L17 1 S L16

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- 10/048, 243, USPAT Text Search  
1-23-06, RPA
- ☐ Drafts
  - ☐ Pending
  - ☐ Active
  - ☐ Failed
  - ☐ Saved
    - ☐ S1: (4489) 430/270.1.ccls. or 430/326.ccls. or 430/921.ccls.
    - ☐ S2: (222) cyclopentyl adj (acrylate or methacrylate)
    - ☐ S3: (12) cyclopentylacrylate or cyclopentylmethacrylate
    - ☐ S4: (6009) cyclohexyl adj (acrylate or methacrylate)
    - ☐ S5: (463) cyclohexylacrylate or cyclohexylmethacrylate
    - ☐ S6: (395) \$7adamantyl adj (acrylate or methacrylate)
    - ☐ S7: (10) S1 and (S2 or S3)
    - ☐ S9: (4) S1 and (S2 or S3) and S6
    - ☐ S8: (45) S1 and (S4 or S5) and S6
    - ☐ S10: (0) cyclohexyl adj (acrylate or methacrylate) near5 \$7adamantyl adj (acr
    - ☐ S11: (0) cyclohexyl adj (acrylate or methacrylate) near10 \$7adamantyl adj (acr
    - ☐ S12: (6) cyclohexylmethacrylate near5 \$7adamantylmethacrylate
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  - ☐ Tagged (0)
  - ☐ UDC
  - ☐ Queue
  - ☐ Trash

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☐ Purge ☐ Highlight all hits in body

1 and (2 or 3)

|   | U                        | 1                        | Document ID | Issue Date | Page | Title  | Current OR | Current XRef | Retrieval C | Inventor           | S                                   | C                        | P                        | 3                        |
|---|--------------------------|--------------------------|-------------|------------|------|--|------------|--------------|-------------|--------------------|-------------------------------------|--------------------------|--------------------------|--------------------------|
| 1 | <input type="checkbox"/> | <input type="checkbox"/> | US 6946234  | 20050920   | 23   | Positive sensitive resin composition and a process for | 430/270.1  | 430/288.1;   |             | Imai, Genji et al. | <input checked="" type="checkbox"/> | <input type="checkbox"/> | <input type="checkbox"/> | <input type="checkbox"/> |
| 2 | <input type="checkbox"/> | <input type="checkbox"/> | US 6946234  | 20050920   | 23   | Positive sensitive resin composition and a process for | 430/270.1  | 430/288.1;   |             | Imai, Genji et al. | <input checked="" type="checkbox"/> | <input type="checkbox"/> | <input type="checkbox"/> | <input type="checkbox"/> |

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L2: (1) "6692897".pn.

L8: (1) "6517993".pn.

L9: (1) "6824956".pn.

L10: (1) "6830866".pn.

cyclopentylacrylate or cyclopentylmethacrylate

\$7 adamantyl adj (acrylate or methacrylate)

cyclohexylmethacrylate near5 \$7adamantylmethacrylate

cyclohexylmethacrylate near5 \$7adamantylmethacrylate

S1: (4489) 430/270.1.ccls. or 430/326.ccls. or 430/921.ccls.

S2: (222) cyclopentyl adj (acrylate or methacrylate)

S3: (12) cyclopentylacrylate or cyclopentylmethacrylate

S4: (6009) cyclohexyl adj (acrylate or methacrylate)

S5: (463) cyclohexylacrylate or cyclohexylmethacrylate

S6: (395) \$7adamantyl adj (acrylate or methacrylate)

S7: (10) S1 and (S2 or S3)

S9: (4) S1 and (S2 or S3) and S6

S8: (45) S1 and (S4 or S5) and S6

S10: (0) cyclohexyl adj (acrylate or methacrylate) near5 \$7adamantyl adj (acrylate or methacrylate)

S11: (0) cyclohexyl adj (acrylate or methacrylate) near10 \$7adamantyl adj (acrylate or methacrylate)

S12: (6) cyclohexylmethacrylate near5 \$7adamantylmethacrylate

Search: [USPAT] [OR] [BRS form] [IS&R form] [Image] [Text] [HTML]

"6830866".pn.

|   | U                        | Document ID | Issue Date | Page | Title                                     | Current OR | Current XRef        | Retrieval C | Inventor                  | S                        | C                        | P                        | 3                        |
|---|--------------------------|-------------|------------|------|---|------------|---------------------|-------------|---------------------------|--------------------------|--------------------------|--------------------------|--------------------------|
| 1 | <input type="checkbox"/> | US 6830866  | 20041214   | 35   | Resist composition and patterning process | 430/270.1  | 430/296;<br>430/325 |             | Kobayashi; Tomohiro et al | <input type="checkbox"/> | <input type="checkbox"/> | <input type="checkbox"/> | <input type="checkbox"/> |

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